

Search Notes	Application No.	Applicant(s)
	10/634,904	TAKAHASHI ET AL.
	Examiner	Art Unit
	D. Rutledge	2851

**SEARCHED**

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
cavity or chamber or compartment; frame or wall or support or housing; build\$3 or construct\$3 or add\$3 or additional, first	7/23/2004	DR
second, embed\$4, air or gas, communicat\$3 or connect\$3, projection adj exposure, lithography, microlithography,	7/23/2004	DR
photolithography, wafer or substrate, mask or reticle, motor, temperature, (sens\$3 or detect\$3 or chang\$3 or adjust\$4,	7/23/2004	DR
chamber or cavity	7/23/2004	DR
Class 29	7/23/2004	DR

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
355	53	7/23/2004	DR